

What is claimed is:

1. A substrate treating apparatus for treating substrates, comprising:

5 a treating tank for receiving and treating the substrates;

 holding means movable, while holding the substrates in a cantilever mode, between a treating position in said treating tank and a transfer position above said treating
10 tank;

 transport means for supporting the substrates and transferring the substrates to and from said holding means in said transfer position;

 detecting means for detecting a posture variation of
15 said holding means; and

 correcting means for correcting a position of one of said holding means and said transport means;

 wherein said correcting means performs a correction according to the posture variation of said holding means
20 detected by said detecting means in time of transfer of the substrates between said holding means and said transport means.

2. A substrate treating apparatus as defined in claim 1,
25 wherein said correcting means includes support means for

supporting said holding means to be rockable about a cantilever point of said holding means, and drive means for rocking said holding means about said cantilever point.

- 5 3. A substrate treating apparatus as defined in claim 1, wherein said correcting means includes:

 a through hole formed in a cantilever proximal portion of said holding means;

- a rigid member inserted into said through hole; and
10 positioning means for moving said holding means, by using said rigid member, in an opposite direction to a direction of movement of a cantilever point of said holding means.

- 15 4. A substrate treating apparatus as defined in claim 1, wherein said detecting means includes a laser displacement gauge or image processing means for performing a detection from a position spaced from said holding means.

- 20 5. A substrate treating apparatus as defined in claim 2, wherein said detecting means includes a laser displacement gauge or image processing means for performing a detection from a position spaced from said holding means.

- 25 6. A substrate treating apparatus as defined in claim 3,

wherein said detecting means includes a laser displacement gauge or image processing means for performing a detection from a position spaced from said holding means.

5 7. A substrate treating apparatus as defined in claim 1, wherein said detecting means is mounted in a proximal portion of said holding means.

8. A substrate treating apparatus as defined in claim 2,
10 wherein said detecting means is mounted in a proximal portion of said holding means.

9. A substrate treating apparatus as defined in claim 3, wherein said detecting means is mounted in a proximal
15 portion of said holding means.

10. A substrate treating apparatus as defined in claim 4, wherein said detecting means is mounted in a proximal portion of said holding means.

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11. A substrate treating apparatus as defined in claim 7, wherein said detecting means is arranged to detect an angular acceleration or a distortion.

25 12. A substrate treating apparatus as defined in claim 1,

wherein said detecting means includes contact type
detecting means for performing a detection while in contact
with said holding means.

5 13. A substrate treating apparatus as defined in claim 2,
wherein said detecting means includes contact type
detecting means for performing a detection while in contact
with said holding means.

10 14. A substrate treating apparatus as defined in claim 1,
wherein said correcting means performs a correction based
on a posture of said holding device unloaded with the sub-
strates.

15 15. A substrate treating apparatus as defined in claim 2,
wherein said correcting means performs a correction based
on a posture of said holding device unloaded with the sub-
strates.

20 16. A substrate treating apparatus as defined in claim 1,
wherein said correcting means performs a correction succes-
sively while said holding device shifts between an unloaded
state and a substrate holding state.

25 17. A substrate treating apparatus as defined in claim 1,

wherein said correcting means includes advance/retreat
drive means for advancing and retreating said support
means along a substrate supporting side.

5 18. A substrate treating apparatus as defined in claim 2,
wherein said drive means includes a cam.

19. A substrate treating apparatus as defined in claim 2,
wherein said drive means includes a piezoelectric element.

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20. A substrate treating apparatus as defined in claim 2,
wherein said support means includes a goniostage or a
spherical seat.